

Supporting Information for

Flexible, Transparent and Conductive Metal Mesh Films with Ultra-High FoM for Stretchable Heating and Electromagnetic Interference Shielding

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Supplementary Figures and Tables

The total EMI shielding effectiveness (SE_T) is the sum of the absorption of electromagnetic energy (SE_A), the reflection (SE_R). Reflectivity (R), absorptivity (A), and transmissivity (T) are determined based on the measured parameters including reflection (S_{11}) and transmission (S_{12}) parameters, the equations are as follows:

$$EMI\ SE_T = SE_A + SE_R \quad (S1)$$

$$R = |S_{11}^2| = |S_{22}^2| \quad (S2)$$

$$T = |S_{12}^2| = |S_{21}^2| \quad (S3)$$

$$A = 1 - R - T \quad (S4)$$

$$SE_T = -10 \log T = -20 \log S_{12} \quad (S5)$$

$$SE_R = -10 \log(1 - R) \quad (S6)$$

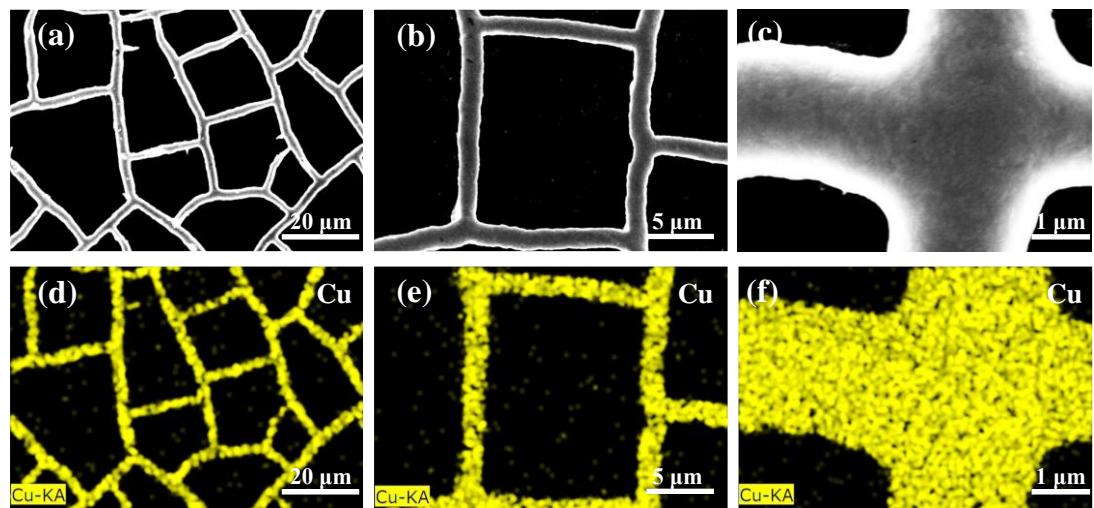


Fig. S1 a-c SEM images of Cu mesh. d-f Corresponding EDS mapping results

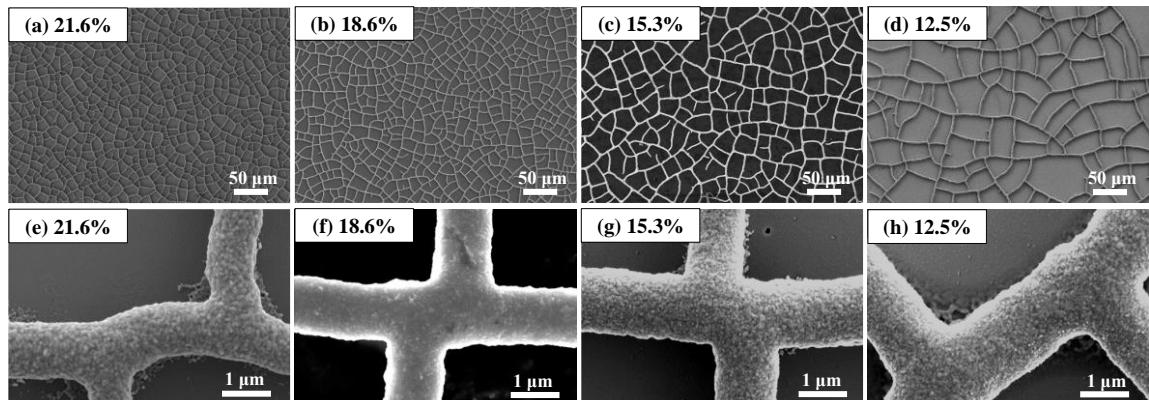


Fig. S2 SEM images of the Cu mesh films with different coverage ratios

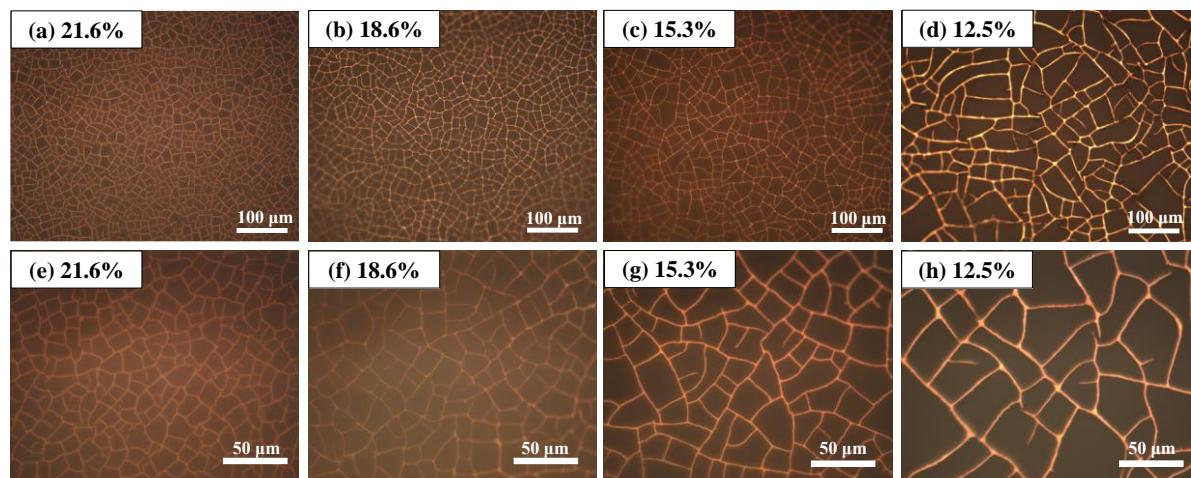


Fig. S3 OM images of the Cu mesh films with different coverage ratios

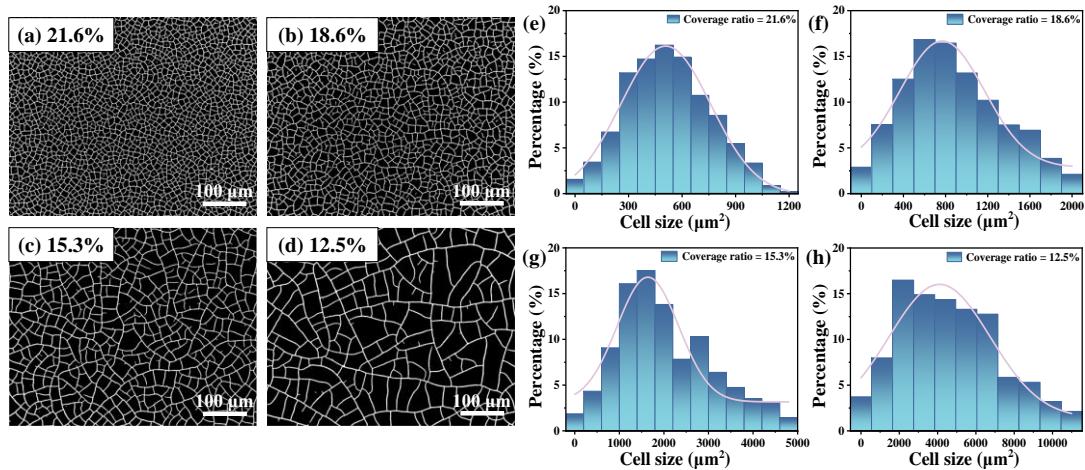


Fig. S4 a-d Images of the Cu meshes processed by image-J (The white areas represent Cu).
e-h Cell size distributions of the Cu mesh with different coverage ratios

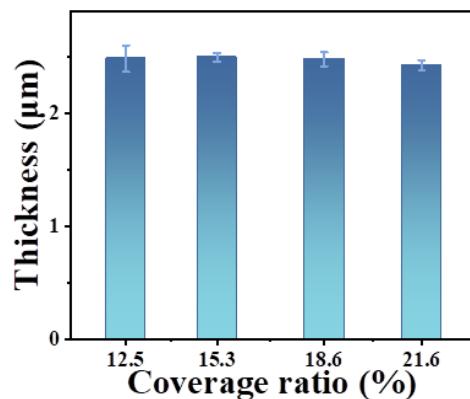


Fig. S5 Thicknesses of the Cu mesh films with different coverage ratios

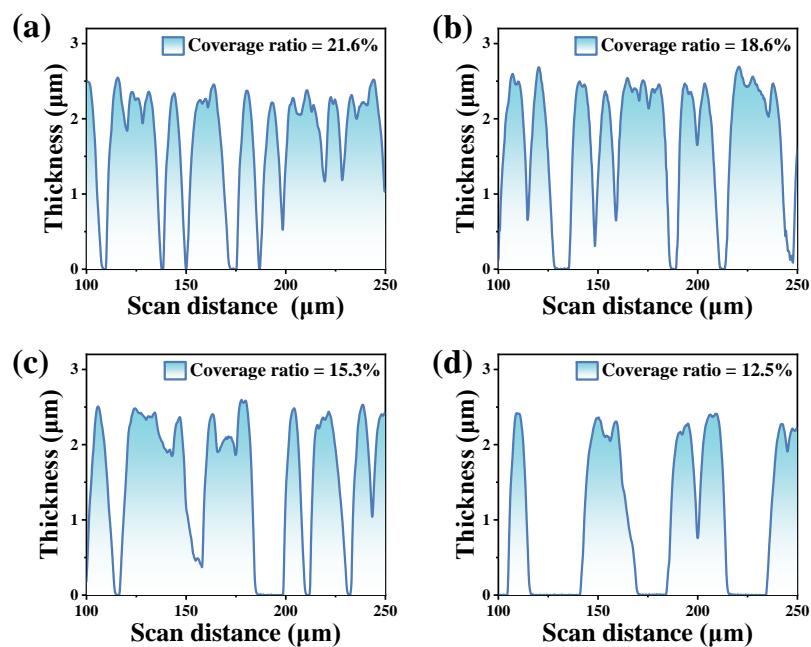


Fig. S6 Thicknesses of Cu meshes with different coverage ratios measured by step profiler
S3/S11

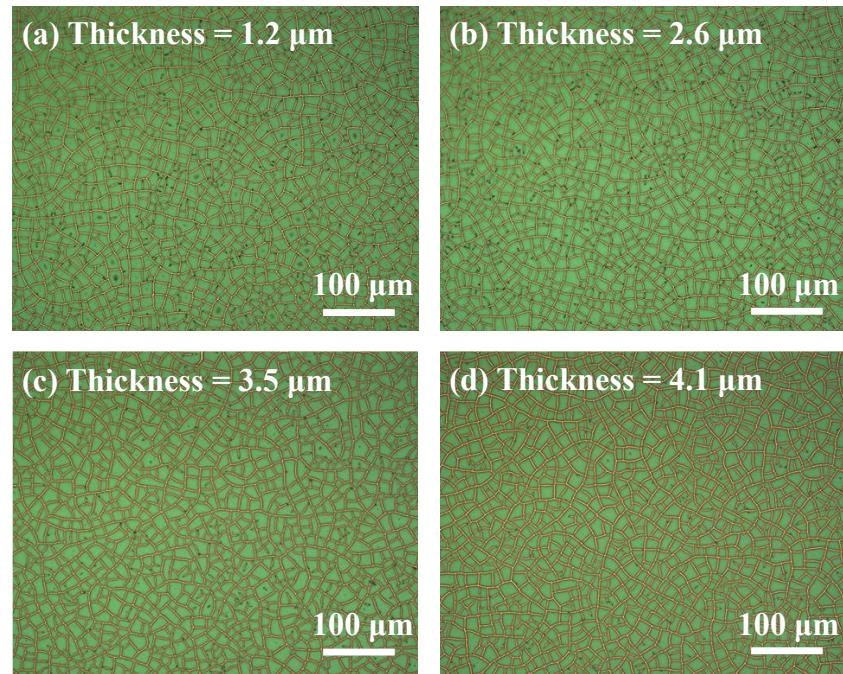


Fig. S7 OM images of Cu meshes embedded in crackle templates at different thicknesses

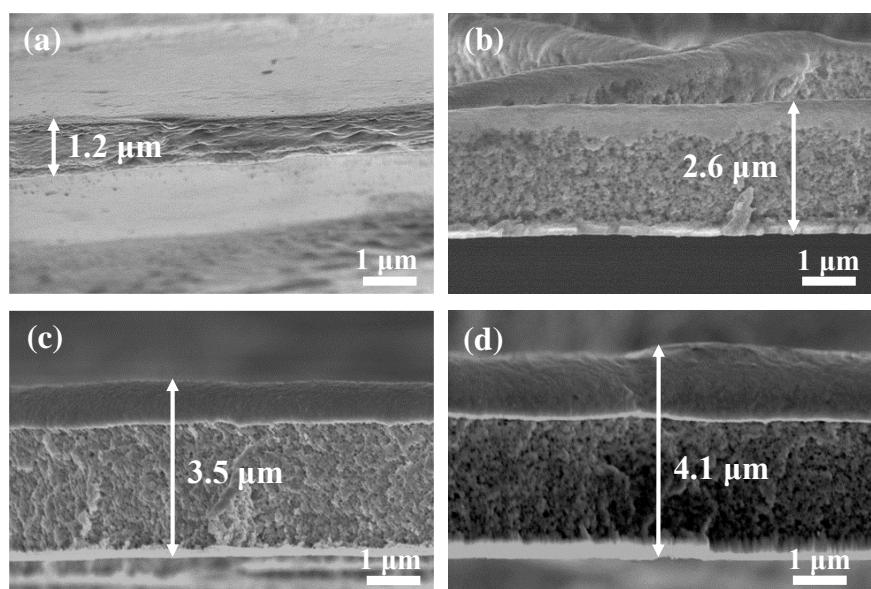


Fig. S8 Cross-sectional SEM images of Cu mesh films at different thicknesses

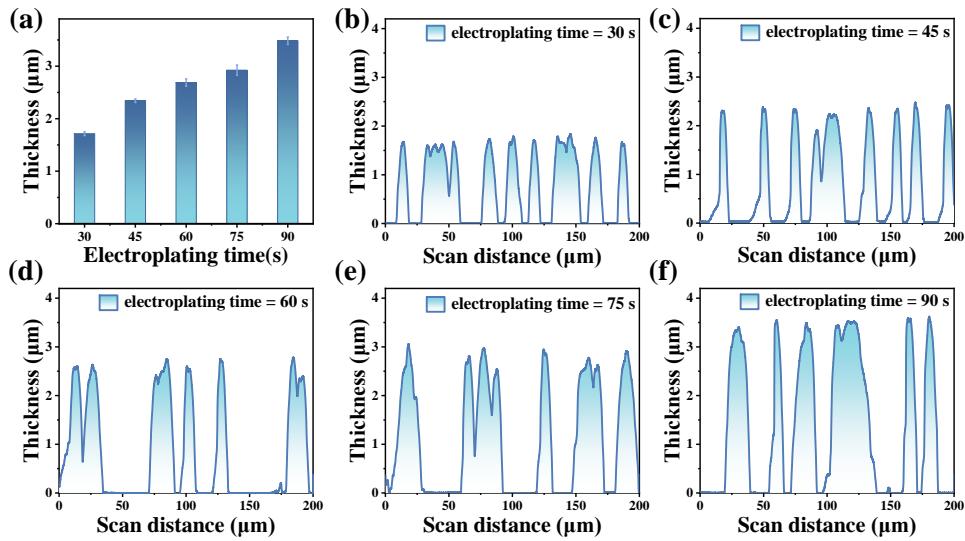


Fig. S9 **a** Thicknesses of the Cu mesh films at different electroplating time. **b-f** Thickness of Cu mesh films with different electroplating time measured by step profiler

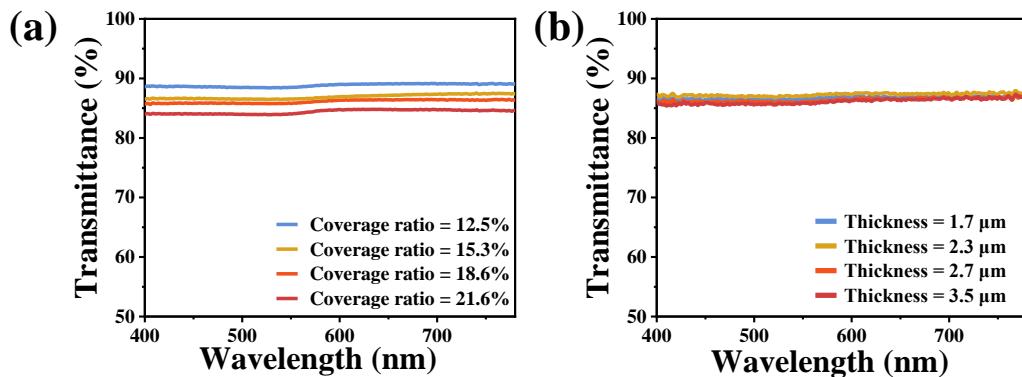


Fig. S10 **a** Transmittance of Cu mesh films with different coverage ratios in visible spectrum. **b** Transmittance of Cu mesh films with different thicknesses in visible spectrum

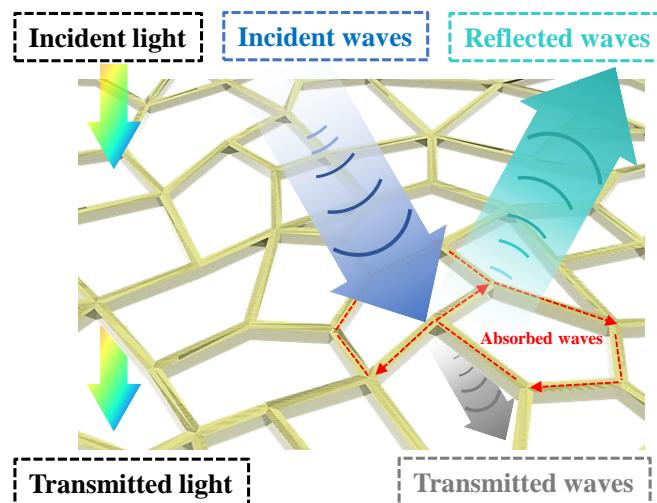


Fig. S11 Schematic diagram of the shielding mechanism for the Cu mesh

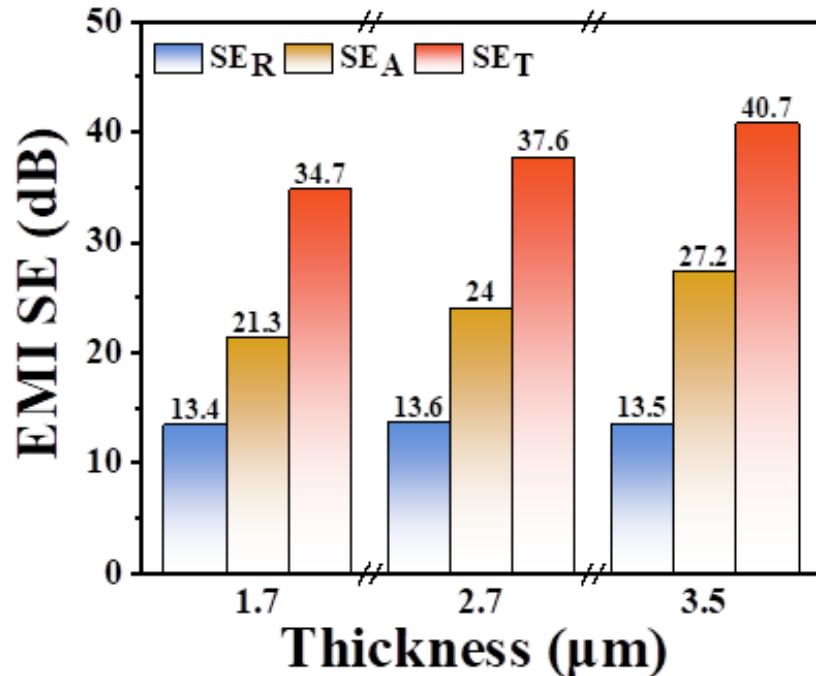


Fig. S12 Contributions of the average EM reflection and absorption to the total EMI SE for Cu mesh films with different thicknesses

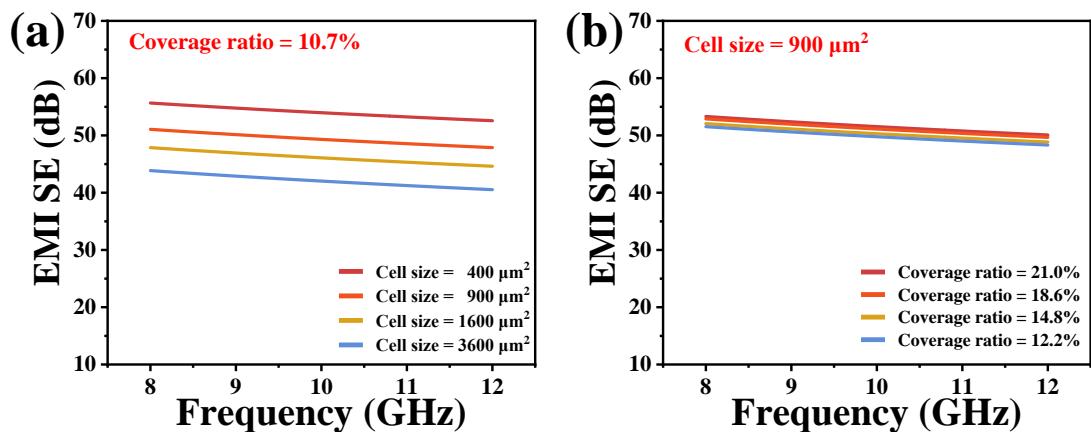


Fig. S13 a Total EMI SE of the Cu meshes (Coverage ratio = 10.7%) with different cell sizes in the X-band (8.2-12.4 GHz). **b** Total EMI SE of the Cu meshes (Cell size = 900 μm²) with different coverage ratios in the X-band (8.2-12.4 GHz)

The EMI SE within X-band of copper mesh film was simulated by CST studio suite. The conductivity of copper was set to 5.98×10^7 S/m, and the permittivity of PDMS was set to 2.65. The unit area was set to 16,129 μm², with a total area of all cell sizes set at 14,400 μm², which means that all samples have a coverage ratio of around 10.7% and different cell sizes (Fig. S13a). In addition, the cell size was set to 900 μm², with various coverage ratio by adjusting the line width of the copper (Fig. S13b).

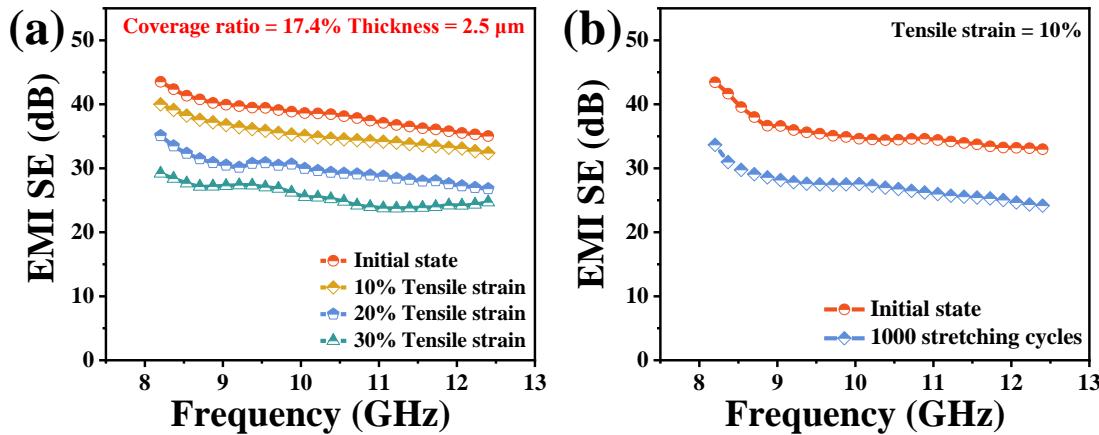


Fig. S14 EMI shielding performance of the flexible Cu mesh films (Coverage ratio = 17.4%, thickness = 2.5 μm). **a** Total EMI SE of Cu mesh at initial state and various tensile strain (10%, 20% and 30%). **b** Total EMI SE of Cu mesh at initial state and after 1000 stretching cycles at 10% tensile strain

Table S1 Parameters for Cu meshes of different coverage ratios

Parameters \ Coverage ratio	12.5%	15.3%	18.6%	21.6%
Crackle lacquer concentration (%)	100	95	90	85
Spin coating speed (rpm)	5000	5000	4500	4000
Culture-dish size (cm^2)	15 \times 15	10 \times 10	10 \times 10	10 \times 10
Temperature ($^\circ\text{C}$)	35	35	35	35
Electroplating time (s)	40	50	60	75
Current density (mA cm^{-2})	20	20	20	20

Table S2 Parameters for Cu meshes of different thicknesses

Parameters \ Thickness (μm)	1.7	2.3	2.7	3.5
Crackle lacquer concentration (%)	95	95	95	95
Spin coating speed (rpm)	5000	5000	5000	5000

Culture-dish size (cm ²)	10 × 10	10 × 10	10 × 10	10 × 10
Temperature (°C)	35	35	35	35
Electroplating time (s)	30	45	60	90
Current density (mA cm ⁻²)	20	20	20	20

Table S3 Comparison of sheet resistances, transmittances and method between TCFS reported in the literatures and this work

Material	Method	Sheet resistance (Ω/□)	Transmittance @550nm	FOM	Refs.
ITO	Drop-coating	20	82%	90	[1]
AgNW	Spin-coating	20.7	94.8%	337	[2]
AgNW/PSSNa	Spin-coating	10	92%	416	[3]
Graphene	Roll-to-roll and wet chemical doping	30	90%	116	[4]
Graphene/AgNW	CVD and Mayer rod coating	8	94%	750	[5]
CNT	Spin-coating	128	90%	27	[6]
MXene	Blade-coating	170	89%	18	[7]
PEDOT:PSS	Spin-coating	75	86%	32	[8]
Ag mesh	UV lithography	2.47	90.3%	1458	[9]
Cu mesh/PU	Imprinting and electroplating	0.15	82.5%	12446	[10]
Metallic mesh	Self-forming and thermal evaporation	2	76%	640	[11]

Cu mesh	Self-forming and electroplating	0.18	85.8%	13232	This work
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Table S4 Comparison of the EMI SE and transmittance of this work with other materials in the literatures

Material	Frequency (GHz)	Average EMI SE (dB)	Transmittance @550nm	Refs.
AgNW@rGO	8.2-12.4	35	91%	[S12]
CA/AgNW/PU	8.2-12.4	21	92%	[S13]
PES/AgNW	8.2-12.4	16	85%	[S14]
AgNW	1-18	30	80%	[S15]
GNS/AgNW	12-18	28	78%	[S16]
Ti ₃ C ₂ T _x	8.2-12.4	4	75%	[S17]
MXene grid/AgNW	8.2-12.4	25	81%	[S18]
Ni mesh	8.2-12.4	36	93%	[S19]
Ag-Ni mesh	8.2-12.4	43	83%	[S20]
AgNW mesh	8.2-12.4	42	67%	[S21]
Cu mesh	12-18	24	82%	[S22]
Cracke template metal mesh	12-18	30	82%	[S23]
Cu mesh	8.2-12.4	41	85.8%	This work

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